Journal of
**Micro/Nanolithography,
MEMS, and MOEMS**

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[DOI: [10.1117/1.JMM.11.2.029801](https://doi.org/10.1117/1.JMM.11.2.029801)]

This article [*J. Micro/Nanolith. MEMS MOEMS* **8**, 029701 (2009)] was originally published online 18 June 2009 with two errors. Equation (6) for the two-dimensional reaction-diffusion point spread function is missing a 2 in the denominator. The correct equation is

$$\text{2-D: } R_{\text{PSF}}(r) = -\frac{1}{2\pi\sigma_D^2} Ei\left(-\frac{r^2}{2\sigma_D^2}\right),$$
$$r = (x^2 + y^2)^{1/2}.$$

Also, Fig. 1 shows the numerical evaluation of the reaction-diffusion autocorrelation function for the 1-D, 2-D, and

3-D cases. Unfortunately, an error in the algorithm used to perform the 2-D and 3-D numerical convolutions needed to generate the 2-D and 3-D autocorrelation functions was in error. When performed correctly, the calculations for the 2-D and 3-D cases produce the exact same results as for the 1-D case. Thus, the 1-D curve shown in Fig. 1 is correct, and the 2-D and 3-D curves should fall exactly on top of the 1-D curve.

Likewise, Table 1 shows the results of fitting these three curves to a function. The fitting parameters obtained for the 1-D case are correct, and the 2-D and 3-D cases should be identical to the 1-D case.